

METHOD AND SYSTEM FOR POST-TREATING DRY-ETCHED METAL FILM

ABSTRACT OF THE DISCLOSURE

A method for post-treating a dry-etched metal film is provided. The dry-etched metal film includes an unetched portion covered by a photoresist and an etched portion exposed from the photoresist and having thereon an etching by-product. According to the method, a stripping agent is used to remove the photoresist on the unetched portion, while reacting the stripping agent with the etching by-product to form a passivation layer on the exposed metal film. Then, a washing agent is used to remove the passivation layer after the photoresist is removed. A system for performing combined etching and stripping procedures of a metal film is also provided. The system comprises dry-etching chambers, stripping and cleaning chambers and a transportation device. In the stripping and cleaning chambers, the photoresist on the unetched portion is removed by a stripping agent and a passivation layer is formed on the etched portion by reacting the stripping agent.